



PATENT
Docket No. 360842006010

AF
JPW

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In the application of:

Masao TOMIKAWA et al.

Serial No. 10/790,800

Filing Date: March 3, 2004

For: POSITIVE PHOTOSENSITIVE RESIN
PRECURSOR COMPOSITION AND
PROCESS FOR PRODUCING THE
SAME

Examiner: John S. Y. Chu

Group Art Unit: 1752

AMENDMENT UNDER 37 CFR 1.116

MS AF
Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Sir:

In response to the Action dated August 23, 2005, please amend this application as follows:

The listing of claims begins on page 2.

The Remarks begin on page 7.